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Latest PANTECHNIK's ECR ion sources performances

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Electron Cyclotron Resonance Ion Sources (ECRIS) are commonly used as injectors in many accelerator laboratories and industries and therefore, pushing its limit towards very high charge state and intense ions for nuclear and elementary particle physics and low charge state ions for surface treatments & medical purposes. For these applications, several models of ECRIS were designed and developed by PANTECHNIK.

This article presents a short description of the latest ECR ion source models delivered to the clients along with their typical beam intensities of low and high charge states of various elements.

A focus will be made on our latest Supernanogan source (14.5GHz) which has just been installed at INSP, France. We will present improvements of highly charged ion production as a function of time and the efficiency of the new gas injection design.

Funding Agency

Footnotes

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Yes

Primary author: MORANA, Ambra (PANTECHNIK)

Co-authors: BERTRAND, Vincent (PANTECHNIK); CAVELLIER, Matthieu (PANTECHNIK); ZANUTTINI, David (PANTECHNIK); LAMOUR, Emily (Institut des NanoSciences de Paris); MACÉ, Stéphane (Institut des NanoSciences de Paris); PRIGENT, Christophe (Institut des NanoSciences de Paris); STEYDLI, Sebastien (Sorbonne University)

Presenter: MORANA, Ambra (PANTECHNIK)

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